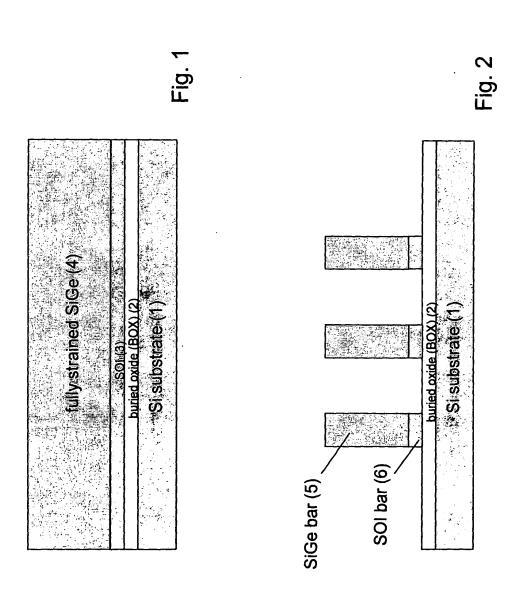
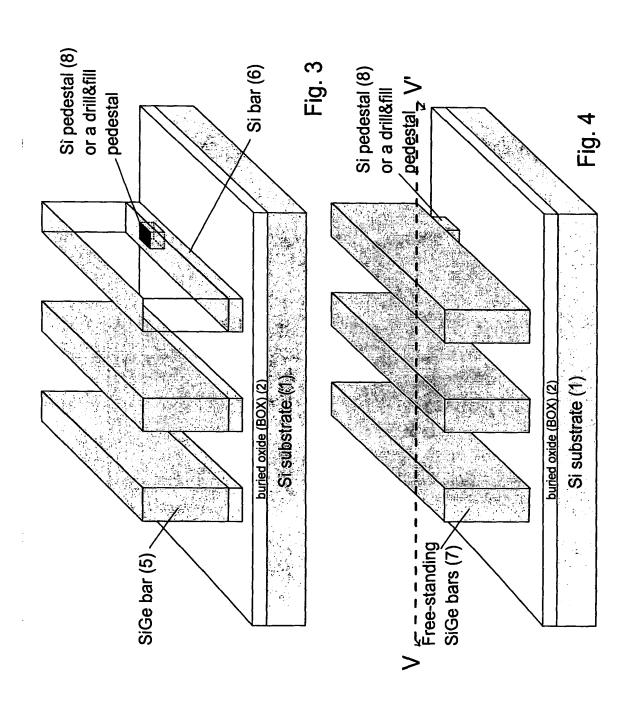
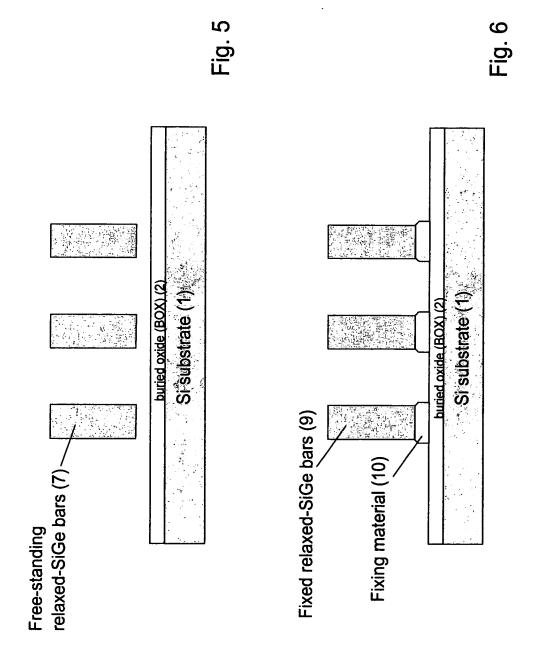
1/13 Guy Cohen TAD YOR920030328US1

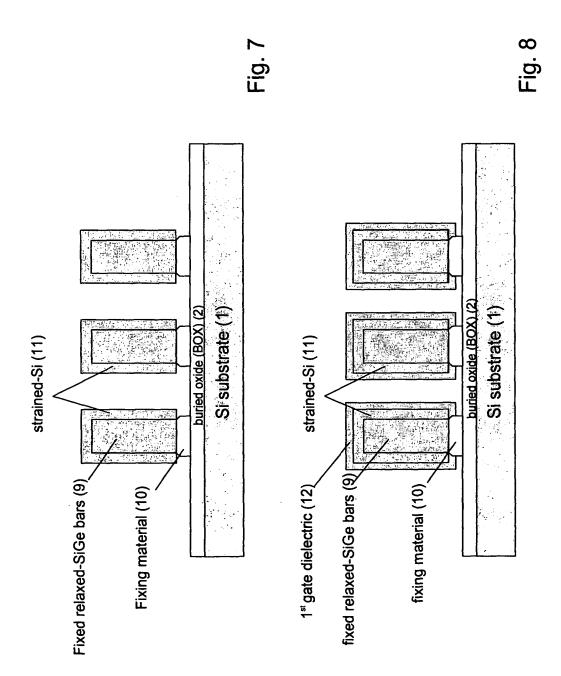


2/13 Guy Cohen YOR920030328US1

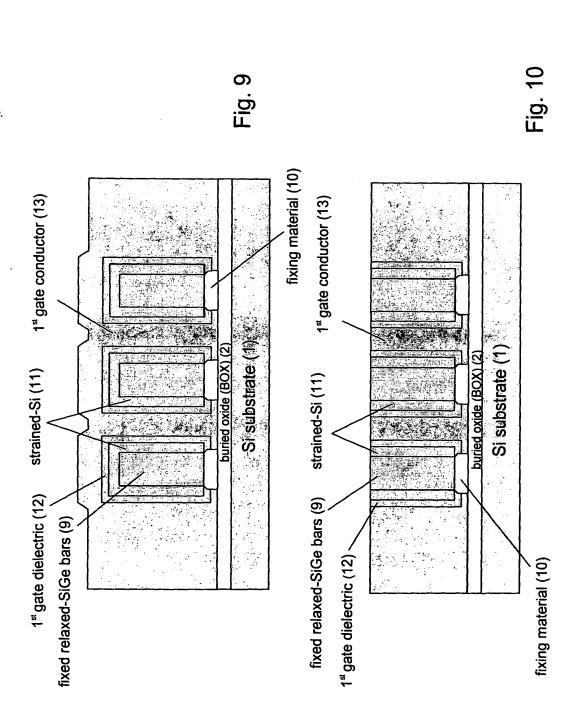


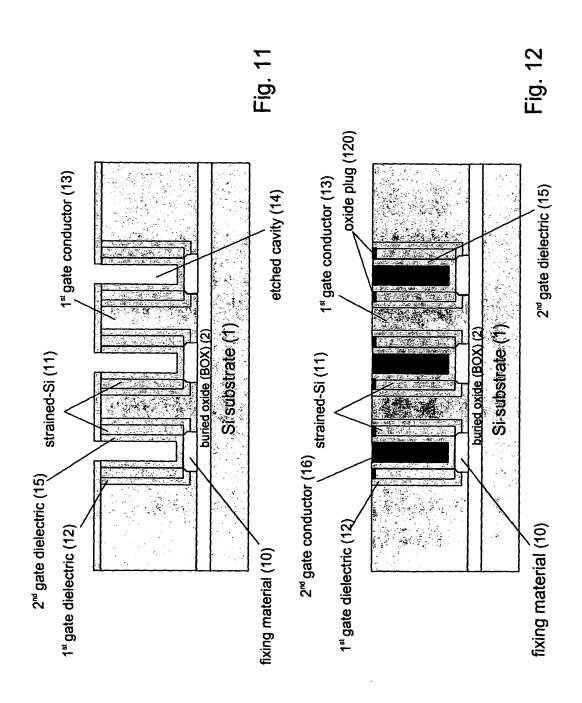


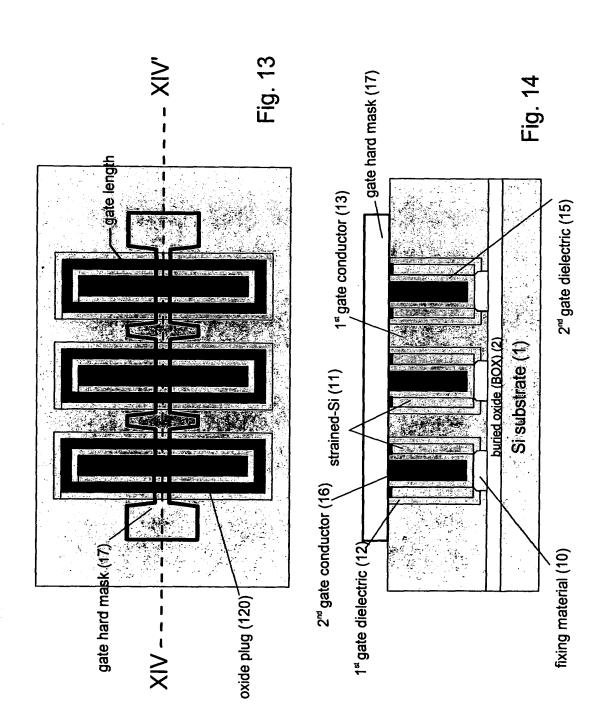
4/13 Guy Cohen YOR920030328USI



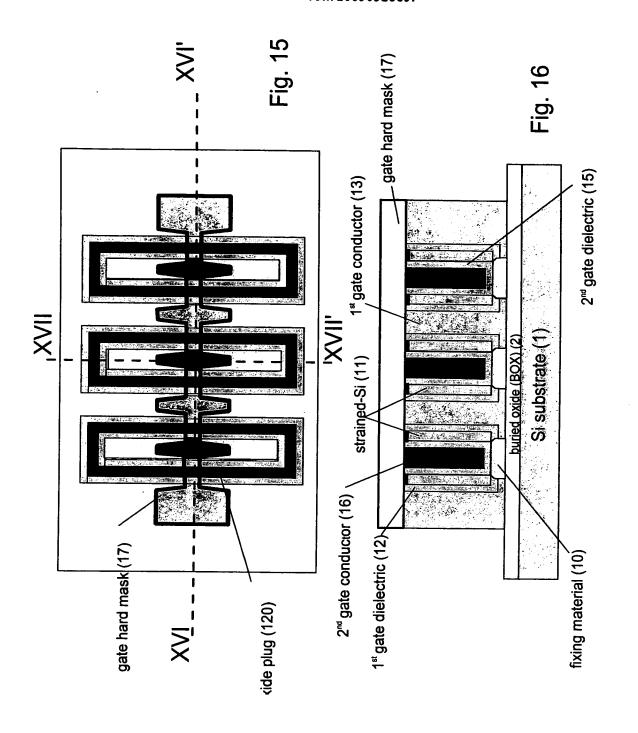
5/13 Guy Cohen YOR920030328US1



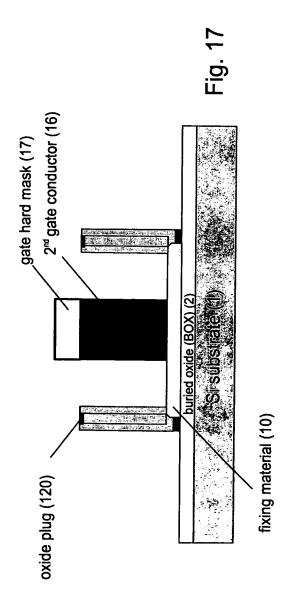




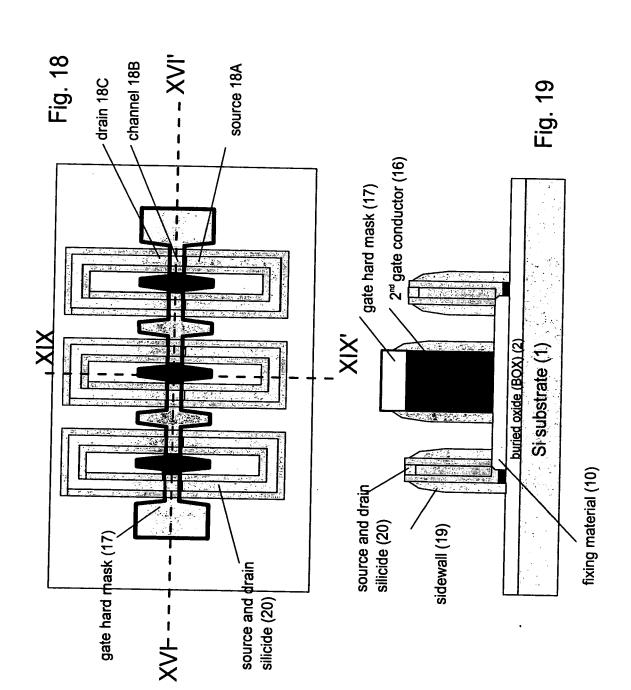
8/13 Guy Cohen YOR920030328USI

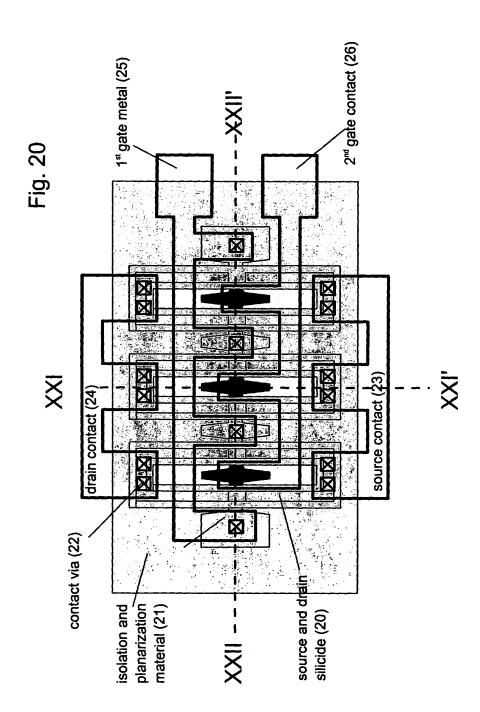


9/13 Guy Cohen YOR920030328US1

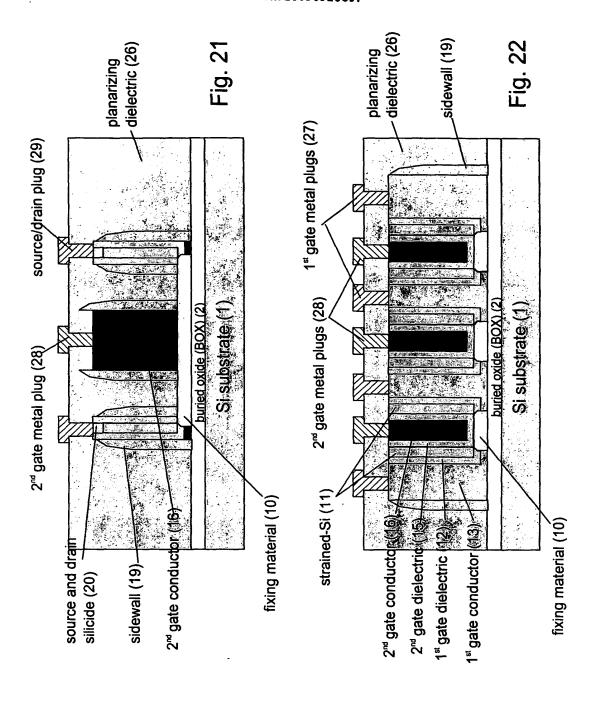


10/13 Guy Cohen YOR920030328USI





12/13 Guy Cohen YOR920030328US1



13/13 Guy Cohen YOR920030328US1

** rielaxed semiconductor (242)*

buried oxide (BOX) (241)

Si substrate (240)

Fig. 23

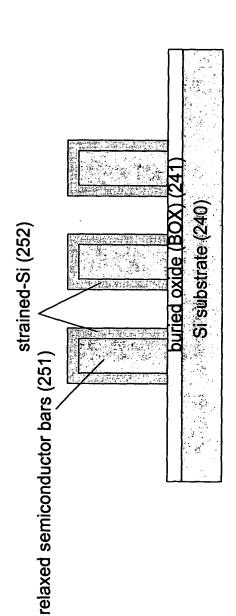


Fig. 24